

	Type	L #	Hits	Search T xt	DBs	Time Stamp
1	BRS	L1	480556	resist or photoresist or resists or photoresists or PR	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:36
2	BRS	L2	47590	(lift-off or liftoff or (lift\$3 adj off))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37
3	BRS	L3	129301	nano\$8	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37
4	BRS	L5	4	(resist or photoresist or resists or photoresists or PR) near8 ((lift-off or liftoff or (lift\$3 adj off))) near8 nano\$8	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37
5	BRS	L4	2	(resist or photoresist or resists or photoresists or PR) near4 ((lift-off or liftoff or (lift\$3 adj off))) near4 nano\$8	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37

	Typ	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L6	2	((resist or photoresist or resists or photoresists or PR) near8 ((lift-off or liftoff or (lift\$3 adj off))) near8 nano\$8) not ((resist or photoresist or resists or photoresists or PR) near4 ((lift-off or liftoff or (lift\$3 adj off))) near4 nano\$8)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37
7	BRS	L7	120	(resist or photoresist or resists or photoresists or PR) same ((lift-off or liftoff or (lift\$3 adj off))) same nano\$8	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:37
8	BRS	L9	2818	2 same 1 same (residual or residue or residues or remain\$6 or portion)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 13:53
9	BRS	L10	58	9 same (molecul\$6)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/09/24 14:03

L11 micro machine or microstructure or
 (micro adj² (machine or structure or device or fabricat\$1)
 or part¹
 L12 L7. (- manaf\$1) (L¹² apparatus adj dot)
 L14 (ring or line)